



INDIAN INSTITUTE OF TECHNOLOGY BOMBAY

MATERIALS MANAGEMENT DIVISION

Powai, Mumbai - 400076

Photonic Curing System

Technical Specifications :

- 1) Photonic pulse repetition rate: > 6 Hz with radiant exposure 1 J/cm^2 & $> 2\text{Hz}$ for 5 J/cm^2
- 2) Uniform beam intensity and angle control
- 3) Flexibility in changing the intensity, exposure length and pulse shape.
- 4) Sensor for measuring the radiative exposure, data acquisition system & software.
- 5) Minimum exposure area per pulse: 110 cm^2 for 150 mm wide lamp, 235 cm^2 for 300mm wide lamp.
- 6) Porous vacuum chuck.
- 7) Temperature range: 15°C - 350°C
- 8) Sealed chamber with removable vacuum chamber lid with quartz windows.
- 9) Integrated bolometer.
- 10) Should have successfully done the annealing of organic-inorganic hybrid perovskite solar cells with this system.